



NASA SBIR 2008 Phase I Solicitation

S2.05 Optics Manufacturing and Metrology for Telescope Optical Surfaces

Lead Center: GSFC

Participating Center(s): JPL, MSFC

This year's subtopic focuses primarily on manufacturing and metrology of optical surfaces, especially for very small or very large and/or thin optics. Missions of interest include JDEM concepts (<http://universe.nasa.gov/program/probes/jdem.html>), Constellation-X (<http://constellation.gsfc.nasa.gov/>), TPF (http://planetquest.jpl.nasa.gov/TPF/tpf_index.cfm) and SAFIR (<http://safir.jpl.nasa.gov/technologies.shtml>). Optical systems currently being researched for these missions are large area aspheres, requiring accurate figuring and polishing across six orders of magnitude in period (i.e., 1st and 2nd order errors through micro-roughness). Technologies are sought that will enhance the figure quality of optics in any range as long as the process does not introduce artifacts in other ranges (i.e., mm-period polishing should not introduce waviness errors at the 20 mm or 0.05 mm periods in the power spectral density). Also, novel metrological solutions that can measure figure errors over a large fraction of the PSD range are sought, especially techniques and instrumentation that can perform measurements while the optic is mounted to the figuring/polishing machine.

By the end of a Phase 2 program, technologies must be developed to the point where the technique or instrument can dovetail into an existing optics manufacturing facility producing optics at the R&D stage. Metrology instruments should have 10 nm or better surface height resolution and span at least 3 orders of magnitude in lateral spatial frequency.

Examples of technologies and instruments of interest include:

- Interferometric nulling optics for very shallow conical optics used in x-ray telescopes;
- Segmented systems commonly span 60 degrees in azimuth and 200 mm axial length and cone angles vary from 0.1 to 1 degree;
- Low stress metrology mounts that can hold very thin optics without introducing mounting distortion;
- Low normal force figuring/polishing systems operating in the 1 mm to 50 mm period range with minimal impact at significantly smaller and larger period ranges;
- In situ metrology systems that can measure optics and provide feedback to figuring/polishing instruments without removing the part from the spindle;
- Innovative mirror substrate materials or manufacturing methods that produce thin mirror substrates that are stiffer and/or lighter than existing materials or methods;
- Extreme aspheric and/or anamorphic optics for pupil intensity amplitude apodization (PIAA).

Proposals should show an understanding of one or more relevant science needs, and present a feasible plan to fully develop a technology and infuse it into a NASA program.Â Â

